

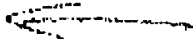
Exhibit A

616]

tsmc 台灣積體電路

TSMC INVENTION DISCLOSURE

[illegible]

4. TITLE OF INVENTION -- (ENGLISH ONLY)
ENGLISH -- PR MIST AUTO DETECTION SYSTEM
5. BACKGROUND INFORMATION -- CURRENT PRACTICE AND DISADVANTAGES (ENGLISH ONLY)
1) Current coater cup design and mist generation mechanism
a. Wafer is rotating when PR & Solvent dispensing
b. PR can coated by wafer spinning.
c. Edge PR can remove by solvent dispense.
d. This solved PR dust should be exhausted by exhausted Air.
e. Splashed back dust become particle or defects because of solvent compound
2) What's the problems?
a. Exhaust line choke up when PR dust piles up ==> Not enough Exhaust.
b. Machine can't check whether splashed back problem happen or not.
c. Splashed back makes process trouble and it makes CP Yield down.
d. If we find out this trouble at ADI inspection, this lot should be reworked
6. MAIN POINTS OF CLAIM (PLEASE LIST ITEM BY ITEM) 主要權利事項(請逐項列明)(ENGLISH ONLY)
1) Use Laser beam to detect scattered PR dust. 
2) Changeable laser generator & detector height.
3) Changeable laser set number. (The more the better)
4) When this detector PR dust system can stop automatically.
5) Attach this system on PR cup.
6) Prevent PR dust P/D by this laser detector.
7. PROBLEM SOLVED OR IMPROVEMENTS OBTAINED BY THIS INVENTION (PLEASE LIST ITEM BY ITEM) (ENGLISH ONLY)
1) Improve Photo Rework rate.
2) Improve CP Yield by reduction of PR dust P/D and EBR splashed back.
8. KEYWORD SEARCH FOR PATENT LITERATURES (ENGLISH ONLY)
Splashed back, PR mist, floating particle
9. PATENT LITERATURES SEARCH RESULT (PLEASE SPECIFY SIMILAR PATENT NO. AND LITERATURE CITATION) (ENGLISH ONLY)
Can't find out (Need to Check again)
10. DETAIL DESCRIPTION OF INVENTION (ENGLISH ONLY)
You can see Attachment file